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Applicant: **EATON CORPORATION**  
Eaton Center, 1111 Superior Avenue  
Cleveland Ohio 44114(US)

Inventor: **Ray, Andrew Marlow**  
6009 Salton Drive  
Austin, Texas 78759(US)

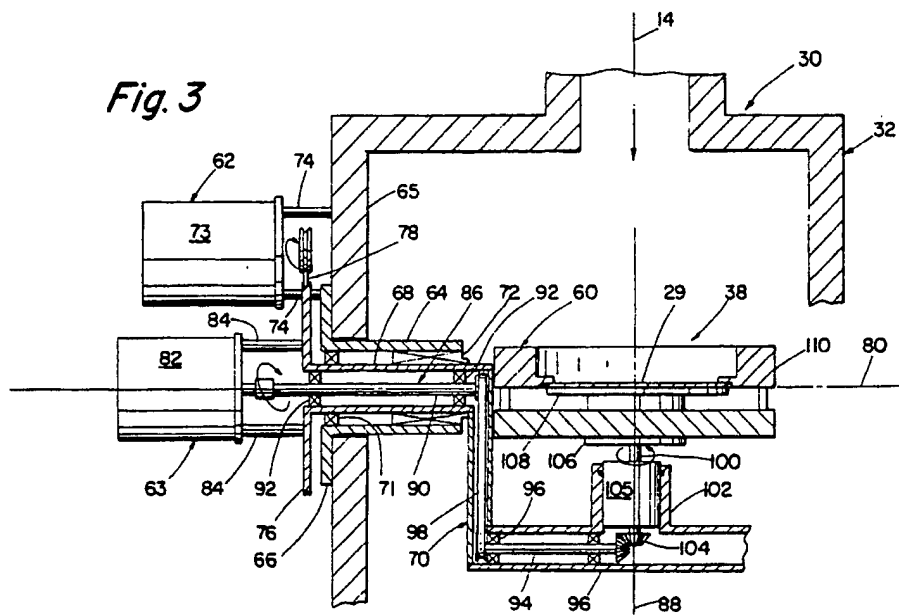
Representative: **Wright, Peter David John et al**  
R.G.C. Jenkins & Co. 26 Caxton Street  
London SW1H 0RJ(GB)

Ion implanter end station.

An end station (30) for an ion implanter which includes a wafer support (38) which is rotatable about a first axis (80) extending substantially along a wafer diameter in the plane defined by the wafer surface, and about a second axis (88) perpendicular to the first axis and extending through the center of

the wafer. The drive systems (62, 63) for providing rotation of the wafer support are operable independently of one another and include stepper motors (73, 82) mounted outside the vacuum chamber (32) of the implanter.

**Fig. 3**



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